[FD3] Plasma Assisted Process Monitoring Technologies	
Date / Time	July 27 (Fri.), 2018 / 14:30-17:00
Place	Room D (#115)
Session Chair(s)	Jung-Sik Yoon (NFRI, Korea)

FD3-1 [Invited] **14:30-15:00**

Cutoff Probe for Process Monitoring

ShinJae You
Chungnam Nat'l Univ., Korea

FD3-2 **15:00-15:20**

Study of Plasma Diagnostics and Algorithm for Virtual Metrology in Etch Process Plasma

Jongsik Kim, Dae Chul Kim, Jung Ho Song, Yonghyun Kim, Young-Woo Kim, Duksun Han, Mi-Young Song, and Jung-Sik Yoon
NFRI, Korea

FD3-3 **15:20-15:40**

Development of Plasma Information Based Virtual Metrology to Trace the Drift of Plasma-Assisted Processes

Hyun-Joon Roh[1], Sangwon Ryu[1], Yunchang Jang[1], Nam-Kyun Kim[1], Younggil Jin[2], Seolhye Park[2], and Gon-Ho Kim[1]
[1]*Seoul Nat'l Univ., Korea,* [2]*Samsung Display Co., Ltd., Korea*

FD3-4 **15:40-16:00**

Measurement of Electron Density of the Cutoff Probe in High Pressure Plasma

SiJun Kim[1], JangJae Lee[1], YoungSeok Lee[1], ChulHee Cho[1], SeungWan Yoo[1], JungHyung Kim[2], and ShinJae You[1]
[1]*Chungnam Nat'l Univ., Korea,* [2]*KRISS, Korea*

FD3-5 **16:00-16:20**

Performance Evaluation Method of RF Generators with In-Situ Plasma Process Monitoring Sensors

Kyung Jae Jo, Syed Ashar Ali, and Sang Jeen Hong
Myongji Univ., Korea

FD3-6 **16:20-16:40**

A Linear Combination Model for Analyzing Long-Time Data Trend in a Plasma Etching Process

Moojin Kim, Gunpil Hwang, Seungjin Kim, and Yongjoon Cheong
Samsung Electronics Co., Ltd., Korea

FD3-7 **16:40-17:00**

Surrogate Modeling of Plasma System with Bayesian Deep Neural Network

Damdae Park and Jong Min Lee
Seoul Nat'l Univ., Korea